



Atomic Layer Deposition & Cousins

Prof. Deshdeep Sahdev (Quazar Technologies)

October 11 at 4 p.m.
 (Hybrid) Lecture Theatre AG66, TIFR
 YouTube Live: <https://youtu.be/ZlCEvdcQ7NU>

The Atomic Layer Deposition System (ALD) was hailed as a breakthrough in thin-film technology because it gave the ultimate control over film thickness: It could be used to deposit metal oxides, nitrides and sulfides, one atomic layer at a time. I will describe our successful, fully indigenous development of an internationally competitive ALD and discuss how its capabilities are being extended in collaboration with ISRO.



Dr. Sahdev trained, as a particle theorist, in leading groups at Cornell University, Univ. of Pennsylvania, and the International Center for Theoretical Physics (Italy) among others.

While at these centers, he worked and interacted with several leading physicists including Profs Salam, Ken Wilson, Steven Weinberg and Richard Feynman. He was a co-discoverer of radiation zeroes and one of the original pioneers of the field of higher-dimensional cosmologies. He has worked on the non-linear dynamics of Josephson-Junction arrays and has developed several algorithms for simulating them. More recently, he has indigenously developed a number of sophisticated instruments including Chemical Vapor and Atomic Layer Deposition Systems.

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